Korean International Semiconductor Conference & Exhibition
on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[TuA1] Nanoscale Thin Film Deposition I	
Session Date	November 11 (Tue.), 2025
Session Time	13:00-14:40
Session Room	Room A (Capri Room, 2F)
Session Chair	Prof. Woo Hee Kim (Hanyang Univ., Korea)

[TuA1-1] [Invited] **13:00-13:30**

Selective Atomic Layer Deposition in Advancing Semiconductor Manufacturing

Rong Chen (Huazhong Univ. of Science and Tech., China)

[TuA1-2] [Invited] **13:30-14:00**

Development of a Selective-Area ALD Process for Buried Word Line in DRAM

Jongho Lee (SK hynix Inc., Korea)

[TuA1-3] [Invited] **14:00-14:20**

Novel Organic Molecular Inhibitors for Improved Step Coverage in High-Temperature ALD Dielectrics

Seung Hyun Lee, Deok Hyun Kim, Kok Chew Tan, Sung Gi Kim, Jung Hun Lim, Young-Soo Park, and Jaesun Jung (Soulbrain Co., Ltd., Korea)

[TuA1-4] **14:20-14:40**

Enhancing Oxide/Nitride Selectivity in Area-Selective ALD via Pyridine-Catalyzed Inhibition

Jieun Oh, Woohyuk Kim, and Woo-Hee Kim (Hanyang Univ., Korea)